



Synthesis and Characterization of $Zn_{1-x}Cr_xO$ Thin Films Deposited by Chemical Spray Pyrolysis Technique

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Abstract

In this study, chemical spray pyrolysis system were using to prepared the $Zn_{1-x}Cr_xO$ films where x (0, 1, 3, 5 and 7) %. Structural and optical properties is studies by XRD and UV\VIS\NIR spectroscopy. Were the average crystal size estimated by Scherers method and the Dave value decreases as CrO increasing and the value about (35.6- 10.7) nm. The energy gap for thin films increases as the CrO increasing starting (0 to 7) % to reach it is maximum value of (3.38eV). The transmittance value of undoped ZnO equal 90% and the The transmittance value decreasing when ratio of doped by CrO increased.

Keywords: Zinc Oxide, Chromium Oxide, Thin Films, Structural Properties.



تصنيع وتوصيف أغشية Zn_{1-x}Cr_xO الرقيقة المحضرة بطريقة التحلل الكيميائي الحراري

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الخلاصة

في هذه الدراسة، تم استخدام طريقة التحلل الكيميائي الحراري في تحضير اغشية Zn_{1-x}Cr_xO بنسب مختلفة (0.00, 0.01, 0.03, 0.05, 0.07). تم دراسة الخصائص التركيبية من خلال حيود الاشعة السينية XRD وتم دراسة الخصائص البصرية باستخدام المجهر UV\VIS\NIR للأغشية الرقيقة المحضرة، حيث تم حساب متوسط الحجم البلوري بطريقة شيرر ووجد ان متوسط الحجم البلوري للأغشية الرقيقة يقل مع زيادة نسبة اوكسيد الكروم بقيم تتراوح بين (10.7- 35.6) nm. وأظهرت نتائج الفحوصات البصرية ان فجوة الطاقة البصرية تزداد مع زيادة نسبة التطعيم بأوكسيد الكروم واعلى قيمة تم الحصول عليها هي 3.38 eV وان قيم النفاذية تقل مع زيادة نسبة التطعيم بأوكسيد الكروم.

الكلمات المفتاحية: اوكسيد الخارصين، اوكسيد الكروم، اغشية رقيقة، الخصائص التركيبية.

Introduction

Transitional oxide ZnO material attracted attention since of magnetic properties base on sp d exchanges interactions. They are deeply examined for spin base electronic application. ZnO have a more scientific application such as gratia transparent electrode and device of piezoelectric. Besides, ZnO is favored than III – V kind material as GaAs and GaN as it is ecofriendly and compatible with technologies of the magnetic storage [1- 3]. ZnO reemerged as an active optical components due to it is energy as a replacements of the GaN for UV light device, such as lights emitting diode, nano lasers [4, 5], photodetectors [6], and nano sensors [7]. The benefits of a ZnO relies on it is excitonics of the required energy at 60*10⁶ eV, permitting for additional efficient excitonics emission, and its vastly extra abundant in natural resource [8]. The objective of the present study the effect of Cr doping ratio of ZnO films prepeard by chemical spray pyrolysis technique then study the optical and structural properties of this films.



Experimental Details

Chemical spray pyrolysis technique were employed to prepared of $Zn_{1-x}Cr_xO$ thin films at deffrent value of $x = (0,1,3,5 \text{ and } 7) \%$ by using high purity of materials, Zinc Nitrate $Zn(NO_3)_2 \cdot 6H_2O$ (99.0%) and Chromium(III) nitrate $Cr(NO_3)_3 \cdot 9H_2O$ (99%). The solutions are prepared by dissolving the amount of Zinc Nitrate $Zn(NO_3)_2 \cdot 6H_2O$ (99.0%) powder with molecular weight 2.974g and amounts of hromium(III) nitrate $Cr(NO_3)_3 \cdot 9H_2O$ (99%) powder withmolecular weight 4.01 g in 100 mL of the distille water at the room temperatures by using magnetic stirrer for (20 min) and resultant of solutions are spraying on glass substrates at 350 °C temperature. Additional conditions for example, distance of spray (28 ± 2 cm), rate of spraying (60 sec), time of spraying (10 sec) and the pressure is (1.6 bar) and saved constant for all samplws. The thickness of all samples were measured by gravimetric technique (300 nm). The X-ray diffractions of the synthesis films are investigete by (Shimadzu/XRD/6000) copper target/ $CuK\alpha/1.5418^\circ A$) and the optical properties investigate by using UV/VIS/NIR spectroscopy (Shimadzu UV1800)

Results and Discussions

Results of XRD

XRD results of $Zn_{1-x}Cr_xO$ where $x = (0,1,3,5 \text{ And } 7) \%$ as showed on Fig 1. The locations of the peak and the occurrence of sevrал diffractions peaks lead to the conclusion that the film have a polycrystalline with hexagonal structure, it can be observed that the lattice constants (a_0 and c_0) decrease as the ratio of CrO increases. From the analysis of the positions of the peaks, 2θ have values of 30.7° , 34.5° and 35.5° which refers to the (100), (002) and (101) preferred planes, and agreement with (JCPDS) card number 00-36-1451. The strong peak happens at $2\theta \sim 34.5^\circ$ which is refer to (002) plane which is in agreement with report [9]. The intensity of peaks decreases when ratios of CrO incresied.

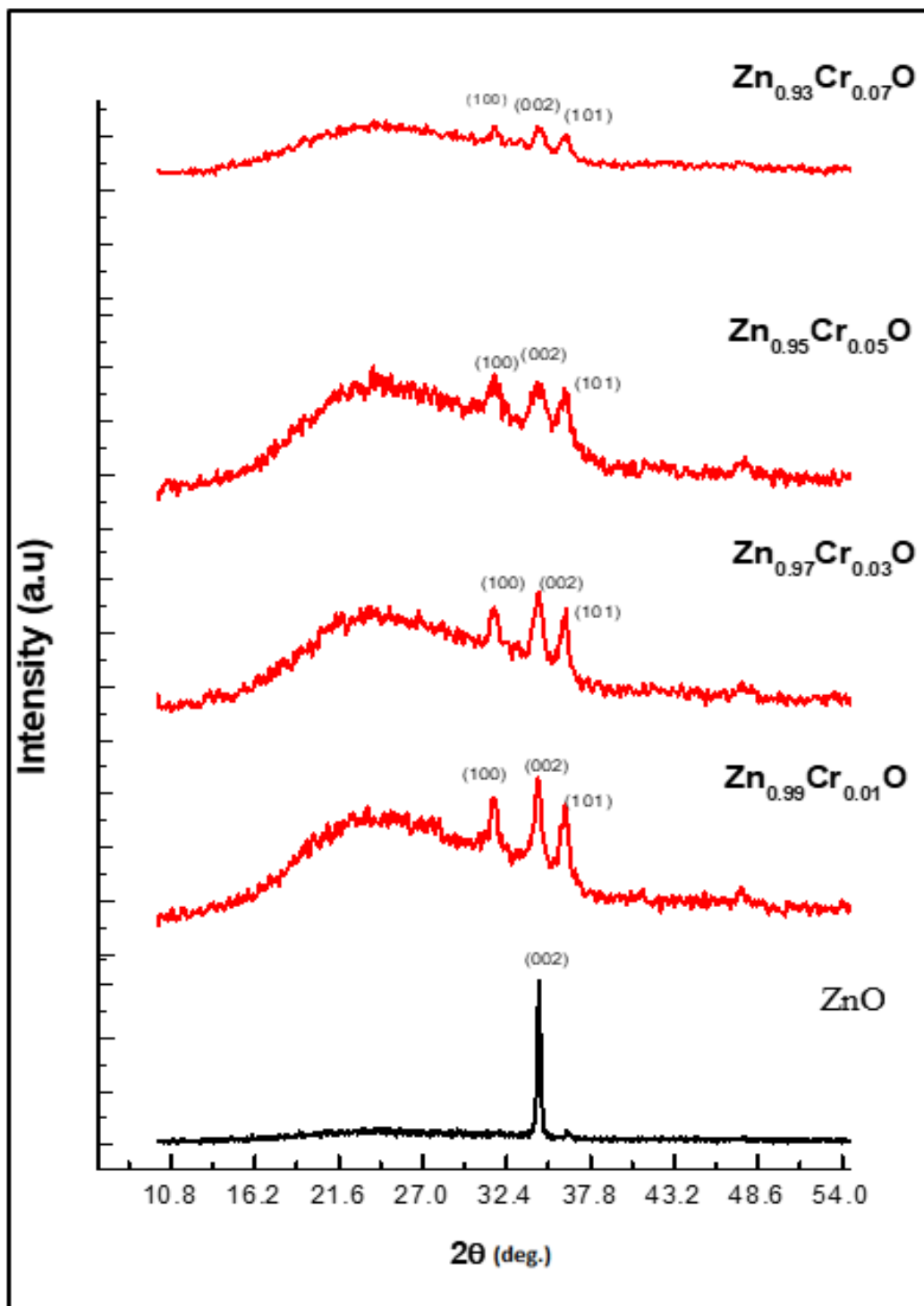


Figure 1: XRD patterns of the of Zn_{1-x}Cr_xO where x= (0, 1, 3, 5 and 7) %



The average of crystallite size (D_{ave}) for the main plane (002) was calculated by using the Scherrer method: [10, 11]

$$D_{ave} = \frac{K \lambda}{\beta \cos \theta} \dots\dots\dots (1)$$

Where λ is wave length of Xray (1.5406 Å), K is factor and equivalent 0.9, θ the Bragg angle and β is the full width of half maximum. The average of crystallite size value decreases as CrO increasing and the value about (35.3- 10.7) nm for [0-7] % respectively, which is agreement with reports [2, 5]. The D_{ave} effected by ionic radius, the radius of chromium ions is equal to and the radius of zinc ions is the radius chromium ($Cr^{+3} = 0.63 \text{ \AA}$) is less than the ionic radius of zinc ($Zn^{+2} = 0.74 \text{ \AA}$), which allows the chromium atoms to enter as substituent atoms within the crystal structure of zinc [13].

The dislocation density (δ) was valued by used eq. [11].

$$\delta = \frac{1}{D_{av}^2} \dots\dots\dots (2)$$

There is a reverse relation between the crystalline size and dislocation density due to that the value of dislocation density increasing when the crystallite size decreases and increasing the ratio of CrO

The number of the crystallite (N_o) was estimated by [12- 16]:

$$N_o = \frac{t}{D_{av}^3} \dots\dots\dots (3)$$

Where t: Thickness of films (350 nm). It's observed that the numbers of the crystallite for film are increasing when ratio of CrO increased.

The texture coefficient (T_c) estimated by [10, 11]:

$$T_{C(hkl)} = \frac{I(hkl) / I_o(hkl)}{N_r^{-1} \sum I(hkl) / I_o(hkl)} \dots\dots\dots (4)$$



Where N the number of reflections, $(I_o_{(hkl)})$ taken from JCPDS data, $(I_{(hkl)})$ is the measured intensity and hkl is the Miller indice. The texture coefficient are using for define the favored directions (hkl) for growing of crystal in a poly crystalline film as showed of the table 1, It was found that the values of the texture coefficient (T_c) is bigger than one for the undoped ZnO films, which indicates that they have one predominant direction which is (002). As for the doped thin films, the T_c is less than one, which means that it has more than one predominant direction (101), (002), (100)

Table1: Result of XRD of of $Zn_{1-x}Cr_xO$ where $x= (0, 1, 3, 5 \text{ and } 7) \%$

Sample	Un doped-ZnO	$Zn_{0.99}-Cr_{0.01}O$	$Zn_{0.97}-Cr_{0.03}O$	$Zn_{0.95}-Cr_{0.05}O$	$Zn_{0.93}-Cr_{0.07}O$
hkl	002	002	002	002	002
2θ (deg)	34.51	34.43	34.42	34.53	34.55
β (rad)	0.0040	0.0064	0.0104	0.0136	0.0122
D_{ave} (nm)	36.3	22.7	14	10.7	11.9
δ (line nm^{-2})	0.0007	0.0019	0.0051	0.0087	0.007
No (nm^{-2})	0.0073	0.0299	0.1287	0.287	0.207
$T_c(hkl)$	2.676	0.787	0.746	0.730	0.793
(a_0) Å	3.249	3.242	3.235	3.232	3.218
(c_0) Å	5.206	5.231	5.206	5.234	5.202

Optical properties of thin film

Figure 2 illustrations the transmittance spectrum as a function of wavelength, within the range (350-600) nm. The transmittance value of undoped ZnO equal 90% and the The transmittance value decreased when ratio of doped by CrO increased, this indicates the increase in the energy gap. The observed result in increasing the energy gap can be attributed to the effect of (Burstein-moss) [17]

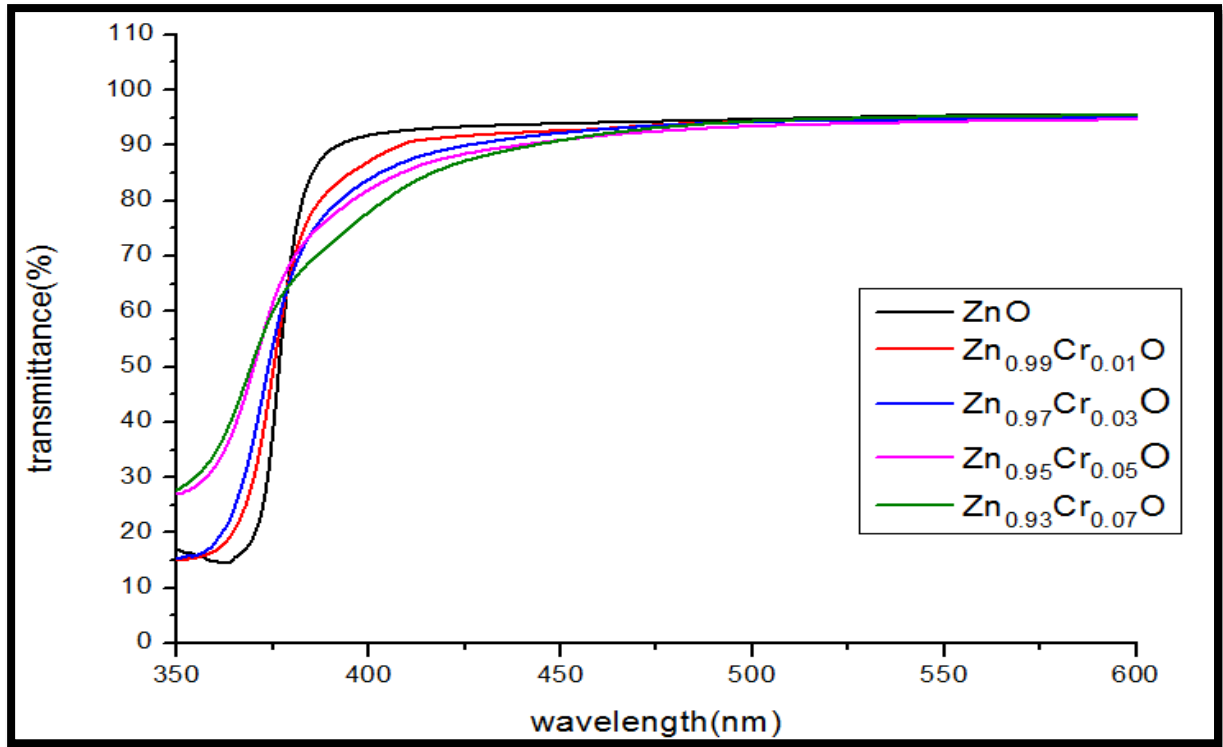


Figure 2: Transmittance for Zn_{1-x}Cr_xO where x= (0, 1, 3, 5 and 7) %

The absorption coefficient (α) were estimated by using [10, 16]:

$$\alpha = 2.303 A / t \dots\dots\dots (5)$$

Where A is absorbance. Figure (3) shows the change of the absorption coefficient as a function of the photon energy of the prepared films, its noticed that the absorption coefficient increases with increasing of the ratio of CrO doping, and then the symmetrical shift occurs in the spectrum of the absorption coefficient in the basic absorption edge due to the effect of (Burstein-Moss) [18].

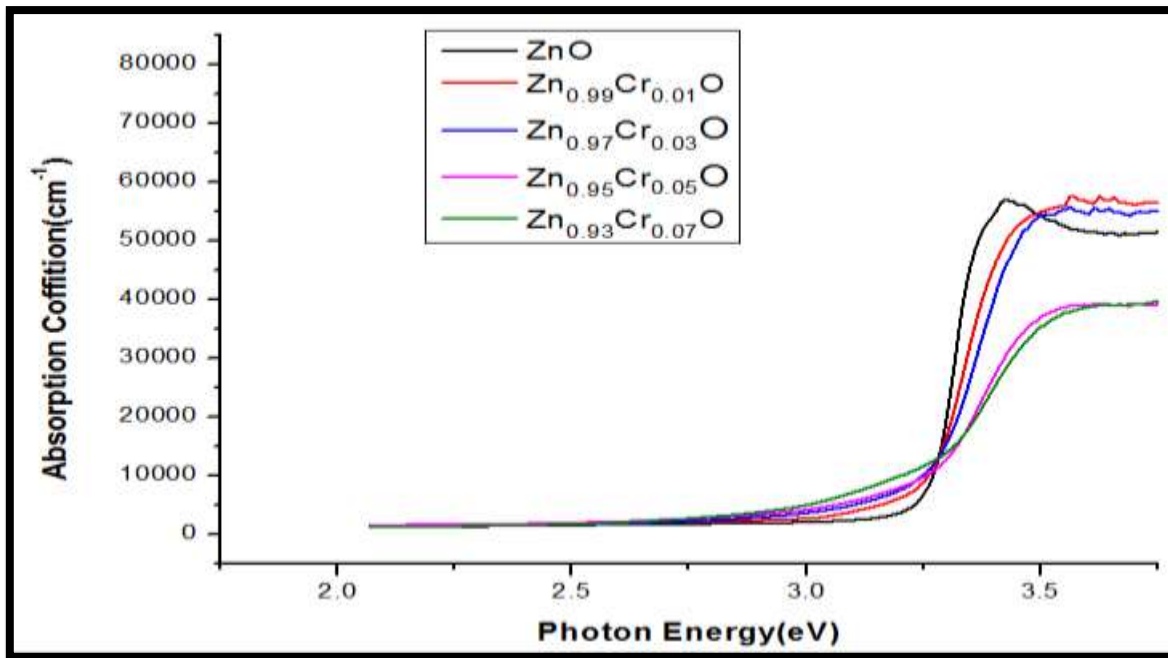


Figure 4: Absorption coefficient of Zn_{1-x}Cr_xO where x= (0, 1, 3, 5 and 7) %

The energy band gap is valued by using eq. [10, 12, 16]:

$$\alpha hv = Z(hv - E_g)^s \dots\dots\dots (6)$$

Where $h\nu$ is the photon energy, Z is the constant and independent of the photon energy. $s=1/2$ to direct transitions. The optical energy gap for the allowed direct electronic transitions for undoped zinc oxide and doped with chromium films was calculated by drawing the linear relationship between $(\alpha hv)^2$ and the photon energy. and the cut-off point represent the value of the energy band gap (E_g) for the films. It is observed that the optical energy gap for thin film increases as the CrO increasing from 0% to 0.07 to reach its maximum value about (3.38 eV), and this increase is due to the effect of (Burstein-Moss) [18, 19], as shown in Table 2.

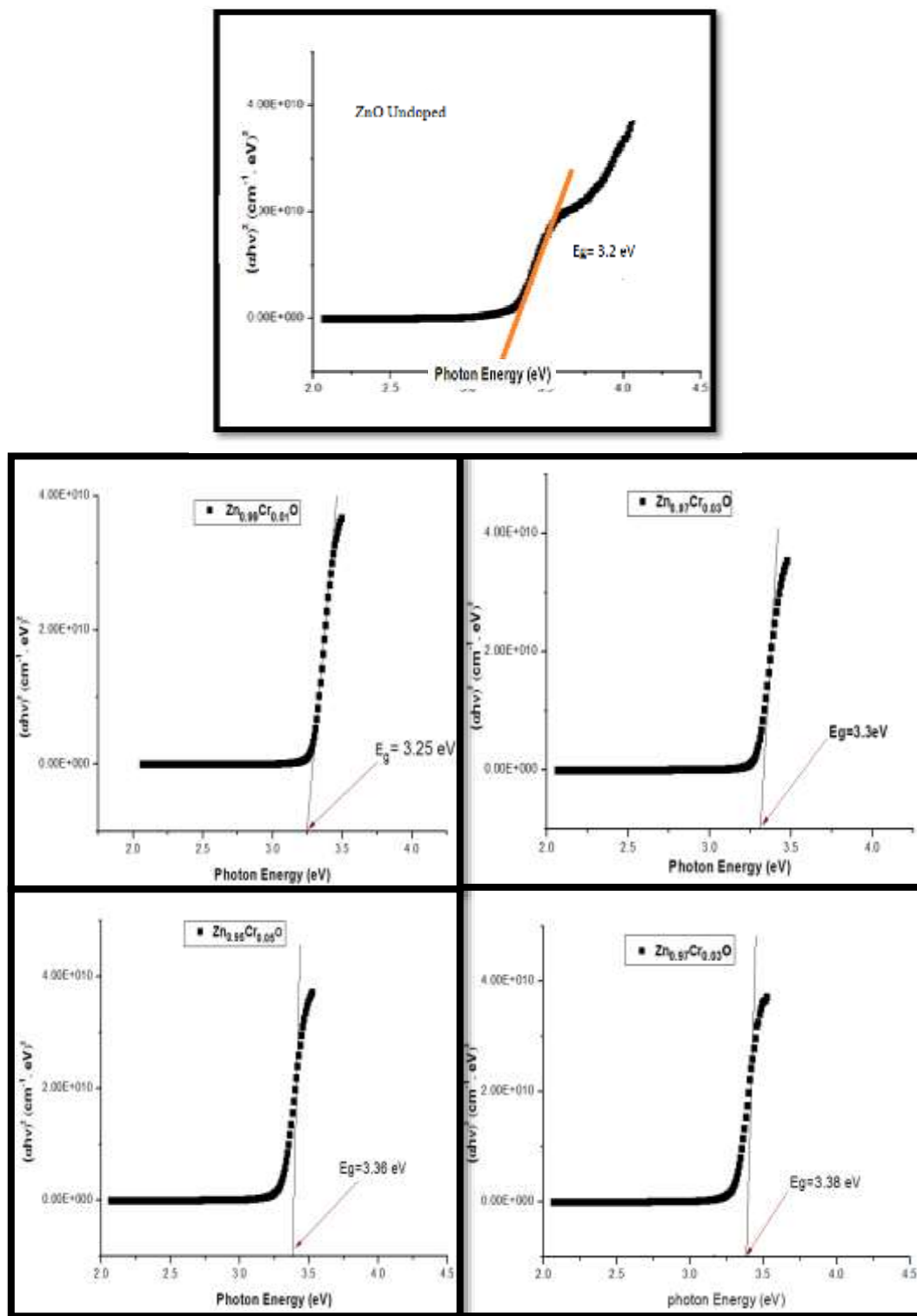


Figure 5: Tauc's plot of Zn_{1-x}Cr_xO where x = (0, 1, 3, 5 and 7) %

Table 2: Optical energy gap value of Zn_{1-x}Cr_xO where x = (0, 1, 3, 5 and 7) %

Films	Undoped ZnO	Zn _{0.99} -Cr _{0.01} O	Zn _{0.97} -Cr _{0.03} O	Zn _{0.95} -Cr _{0.05} O	Zn _{0.93} -Cr _{0.07} O
Eg (eV)	3.2	3.25	3.3	3.36	3.38

The coefficient of extinction (K_o) is estimating by [10, 14, 16, 20]:

$$K_o = \frac{\alpha\lambda}{4\pi} \dots\dots\dots (7)$$

Where λ is wavelengths for incident photon. Figure 6 displayed extinction coefficient as function of wavelength for Zn_{1-x}Cr_xO where x= (0, 1, 3, 5 and 7) %. Its observed that the coefficient of extinction (K_o) decreases at small wavelength (350 to 400) nm and next that the (K_o) keep on constant. The values of K_o increases when the CrO increasing and it was maximum (~ 00.25) for the film prepared at x=0.05. This increasing is due to the increased in the value of the absorption coefficient at these energies, which indicates the occurrence of direct electronic transitions [19].

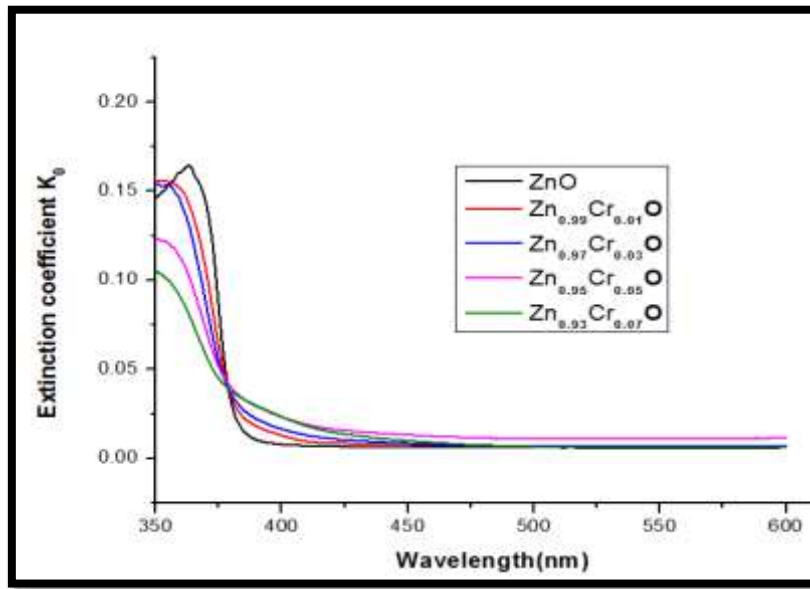


Figure 6: Extinction coefficient for Zn_{1-x}Cr_xO where x= (0, 1, 3, 5 and 7) %



Conclusions

The chemical spray technique was used to prepare Zn_{1-x}Cr_xO films where x = (0, 1, 3, 5 and 7) %. Results of XRD indicated that all samples are polycrystalline in nature with hexagonal structures. The energy band gap of the thin film increases as the CrO increases and the maximum value is (3.38 eV). The transmittance value of undoped ZnO thin film is equal to 90% and may be used as a window of the solar cell.

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